

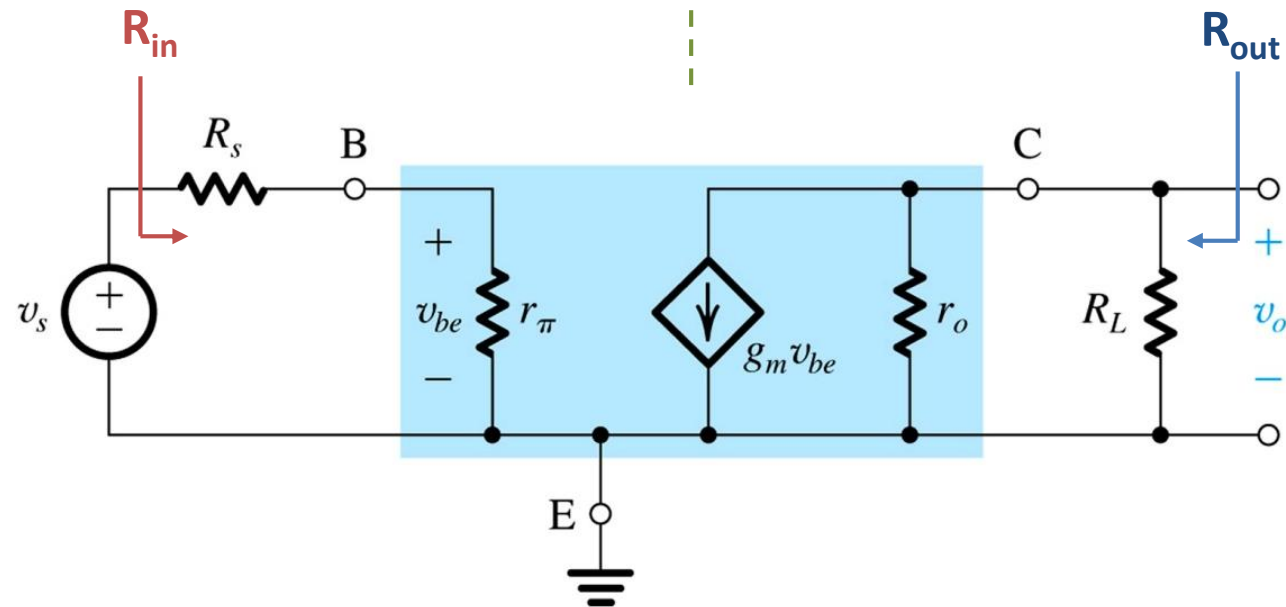
## Last Lecture → Input / Output Impedance of a Circuit

- How can one calculate input resistance from terminal behavior?

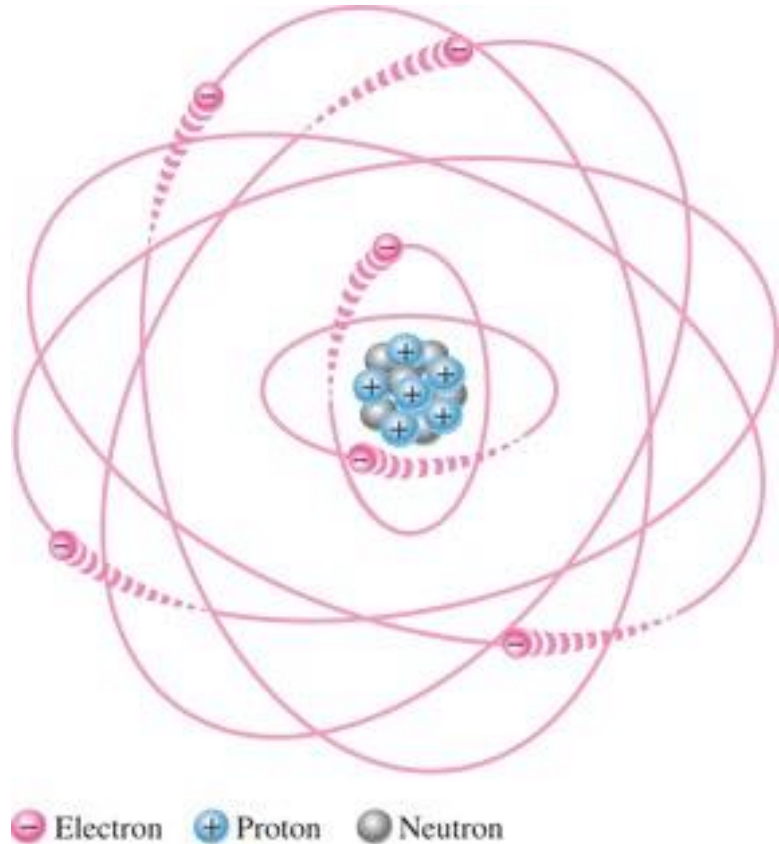
1. place a test source  $V_x$  at the input terminals
2. observe  $v_x$  and  $i_x$
3. calculate via  $R_{in} = v_x / i_x$

- How can one calculate output resistance from terminal behavior?

1. place a test source  $V_y$  at the output terminals
2. turn of the input source ( $V_s=short!$ ,  $I_s=open!$ )
3. observe  $v_y$  and  $i_y$
4. calculate via  $R_{out} = v_y / i_y$

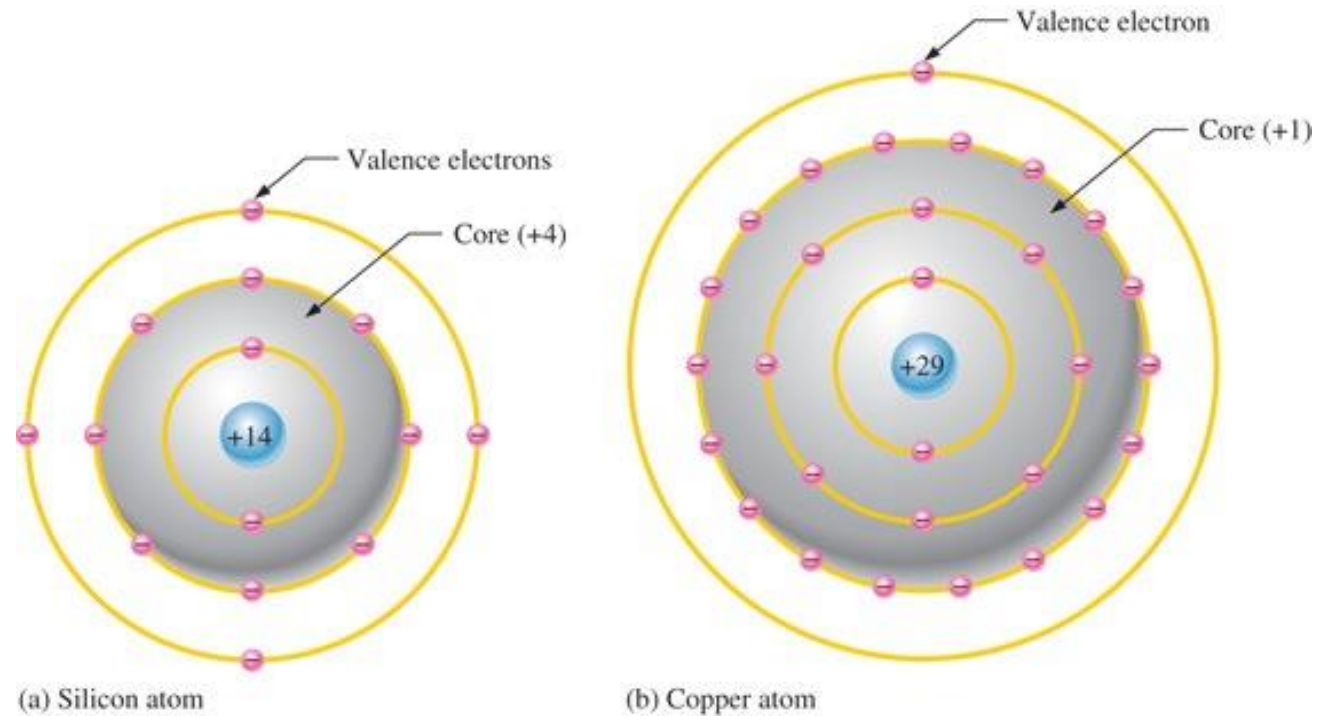


# Atom – Bohr Model → Chp. #3



... **electrons** move in orbits around the nucleus, which consists of **protons** and **neutrons**.

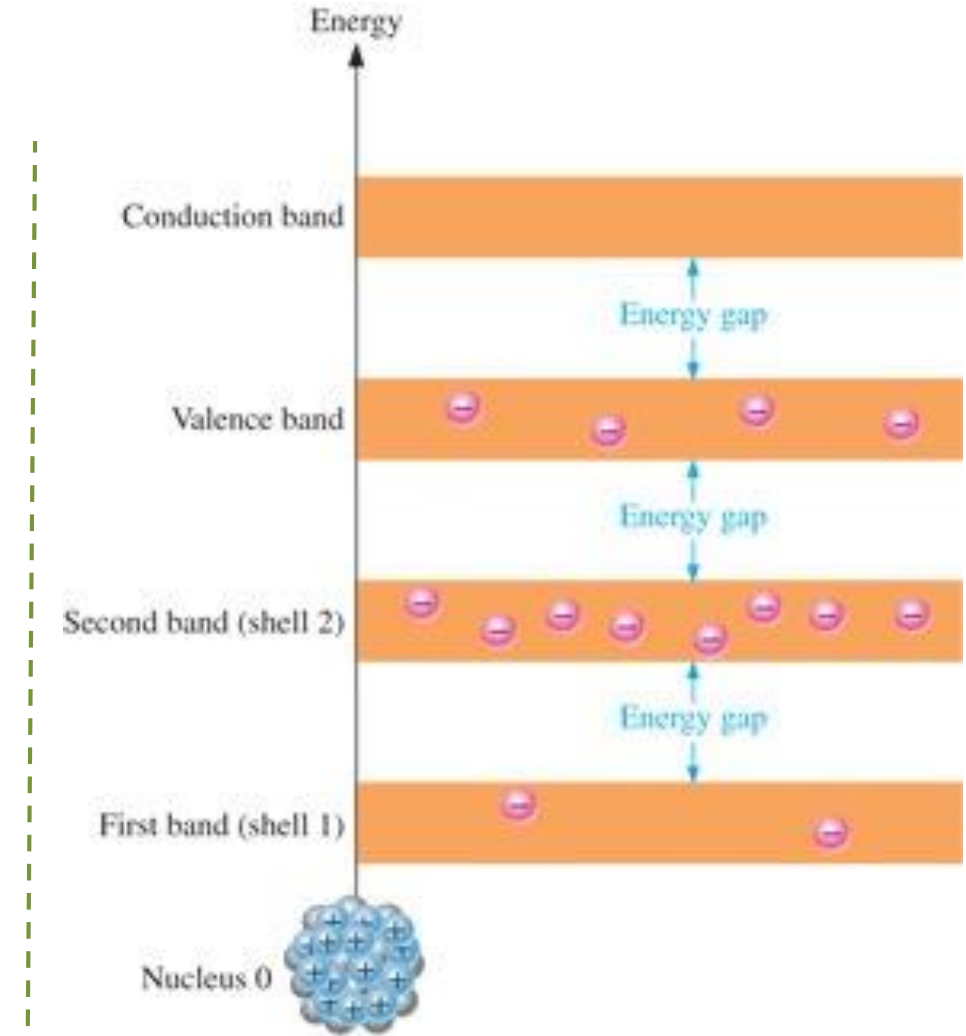
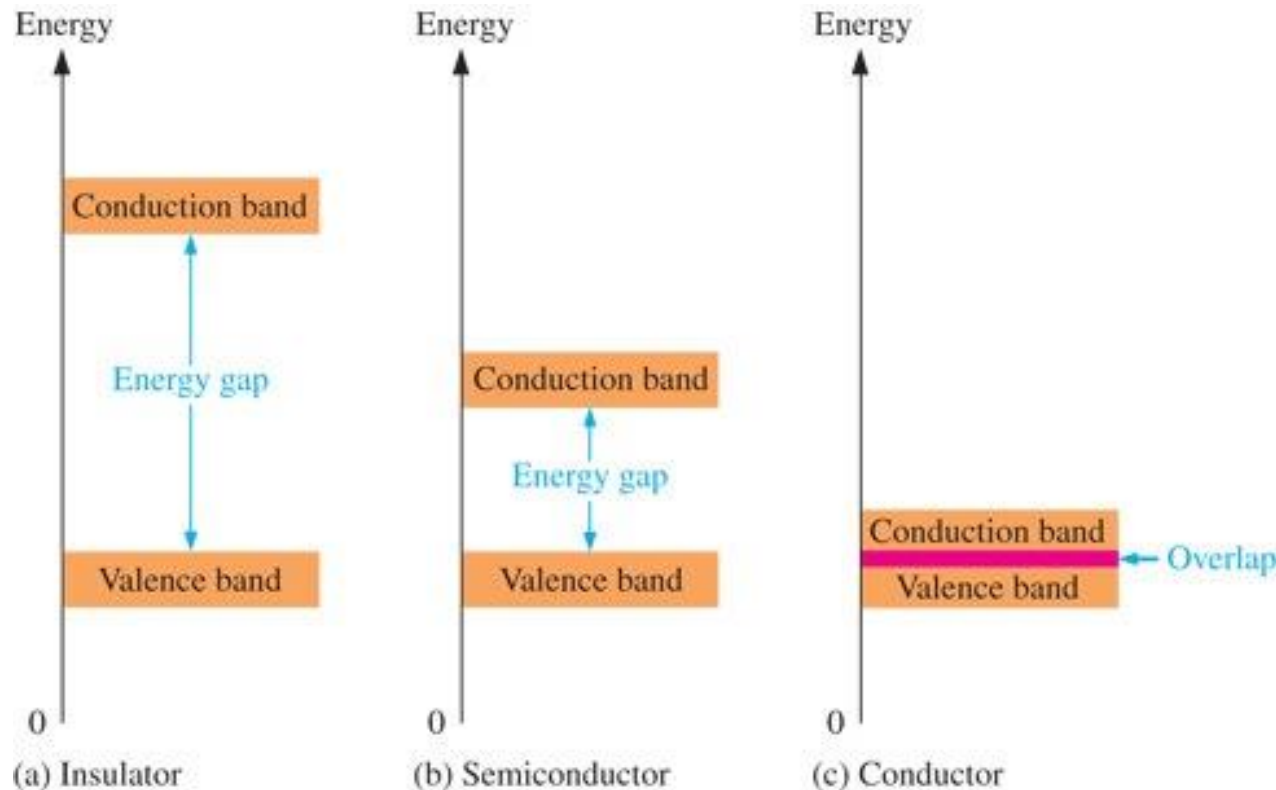
- Elements in the periodic table are grouped according to the number of **valence electrons**.
- **Valence electron** – an electron that participates in the formation of **chemical bonds**.



# Energy Diagram

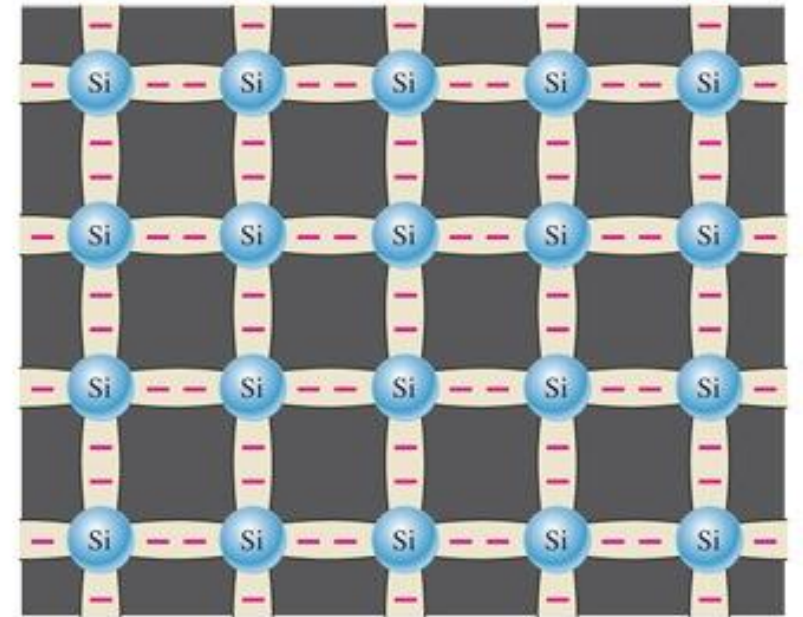
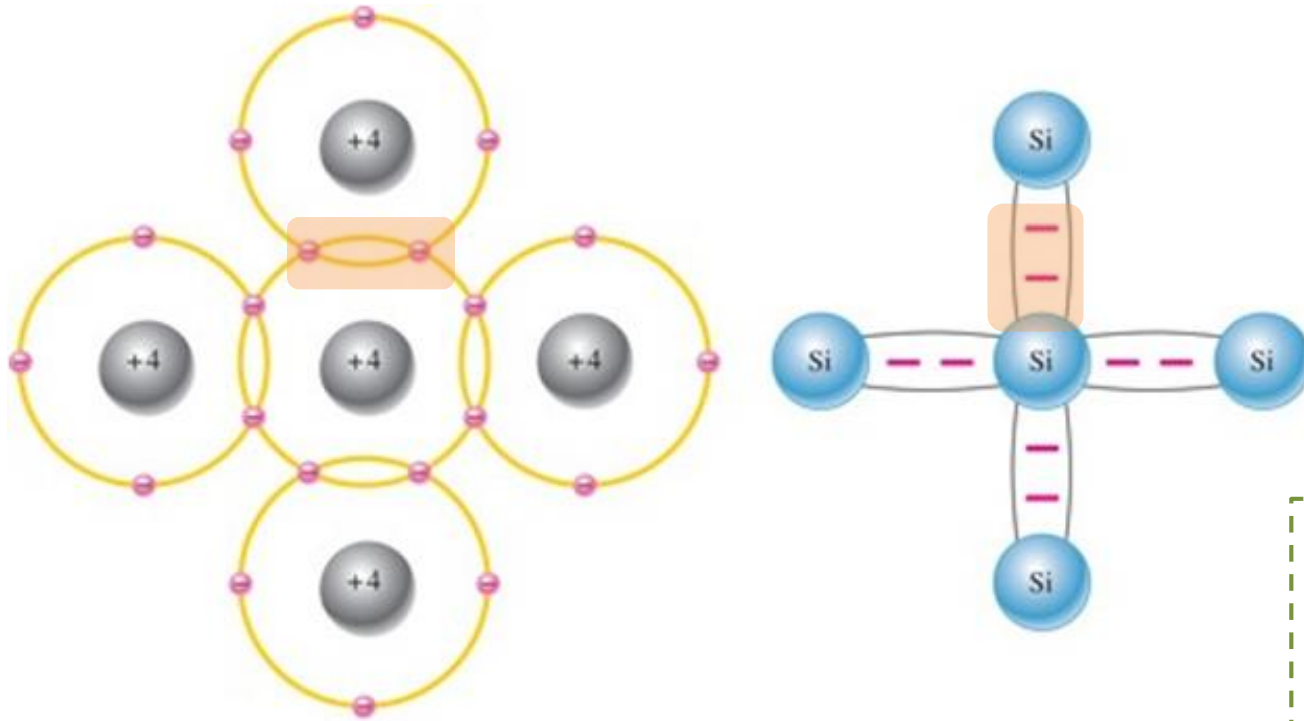
Si

- **Energy Gap ( $E_g$ )** – minimum energy needed by a valence electron in order to jump into the conduction band.
- **Types of Material**



# Covalent Bonds

- As silicon atoms come into proximity to each other, the valence electrons interact to form a crystal
- The **valence electrons are shared between atoms**, forming what are called **covalent bonds**, a stable balance of attractive and repulsive forces between atoms.

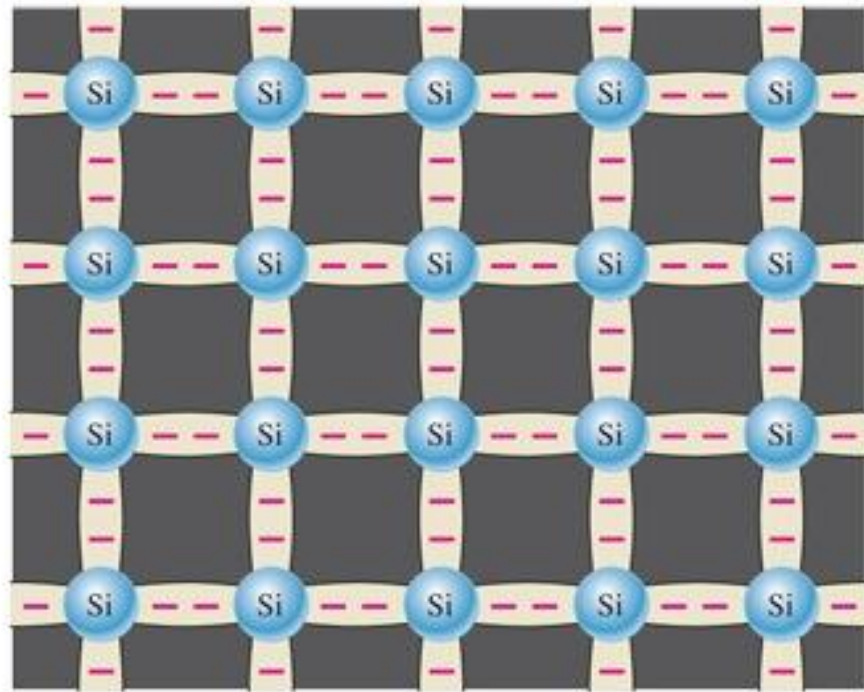


**Intrinsic Semiconductor**: is a single-crystal semiconductor with no other types of atoms within the crystal.



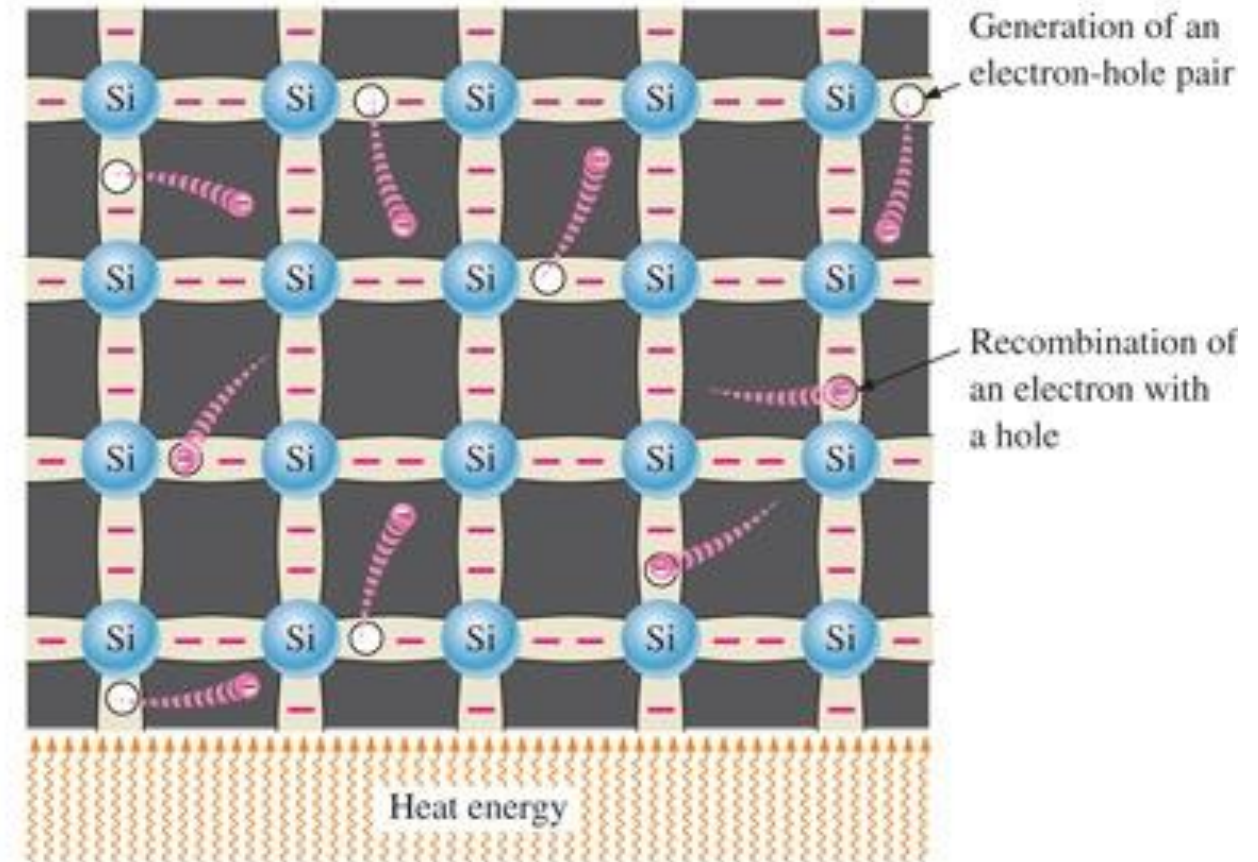
# Silicon Crystal

@ low temp.



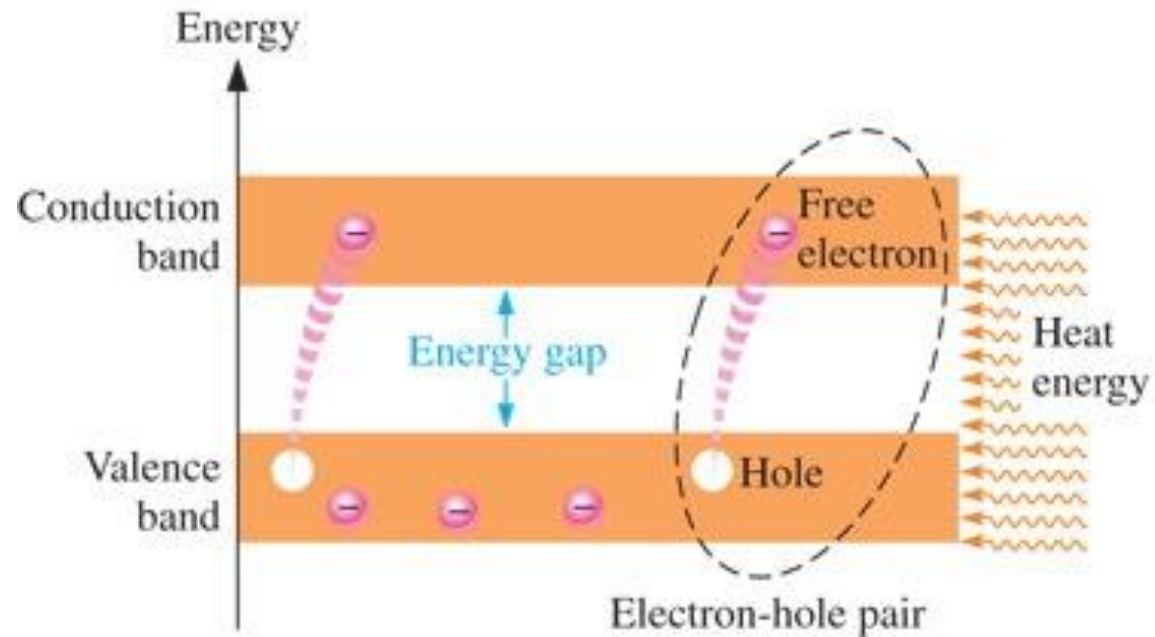
- All **covalent bonds** are intact
- No **electrons** are available for conduction
- **Conductivity** is zero

@ room temp.

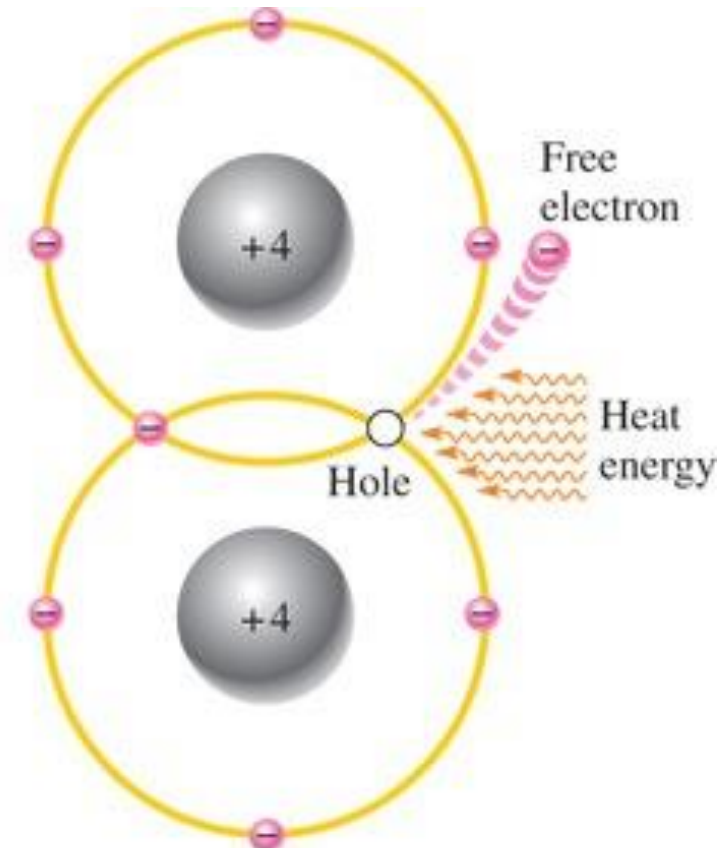


- Some **covalent bonds** break
- Some **electrons** will become available for conduction
- **Conductivity** is greater than zero

# Hole – Electron Pair Creation



(a) Energy diagram

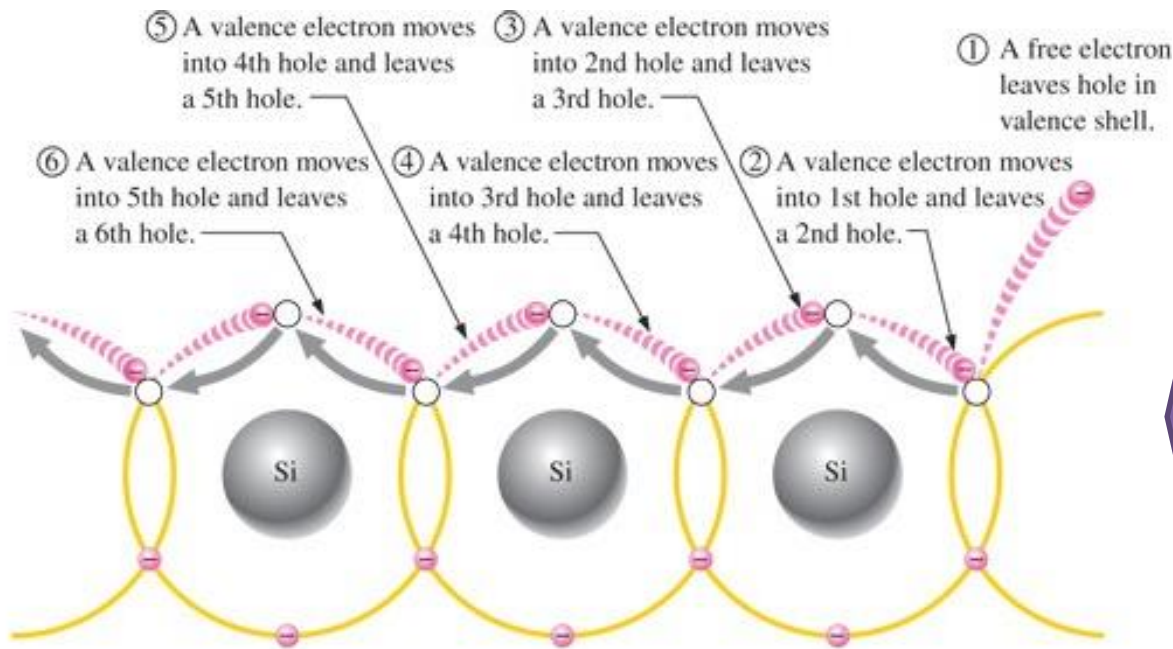
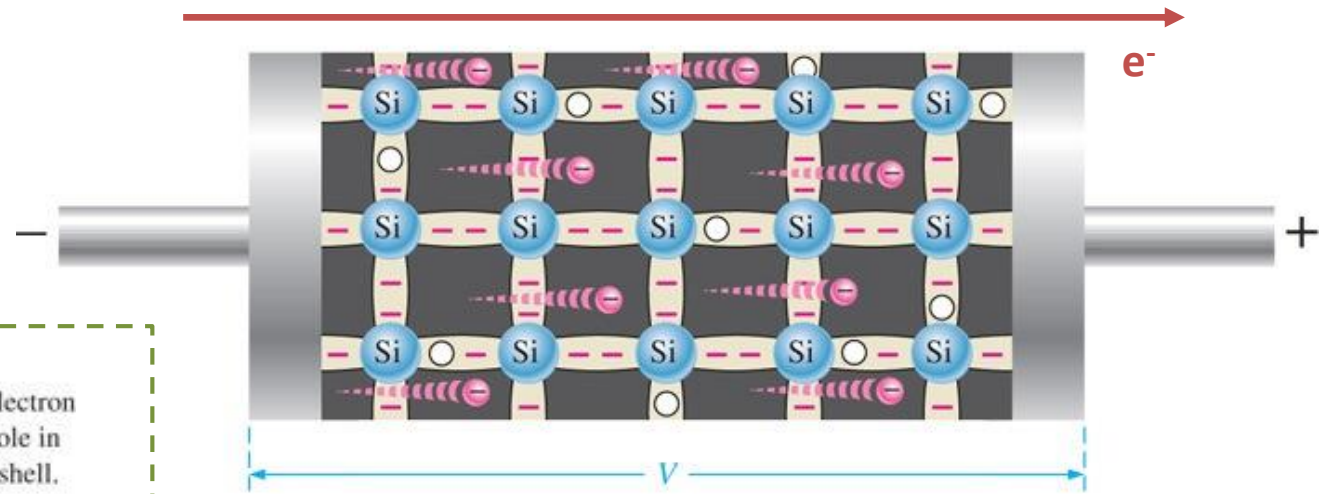


(b) Bonding diagram

The process of freeing electrons, creating holes, and filling them **facilitates current flow...**

# Electron Current

- Movement of **free electrons** in the **conduction band**



When a valence electron moves left to right to fill a hole while leaving another hole behind, the hole has effectively moved from right to left. Gray arrows indicate effective movement of a hole.



# Hole Current

- Movement of electrons in the **valence band**

# Silicon Crystal - Charge Concentration

- concentration of free electrons  $\rightarrow n$
- concentration of free holes  $\rightarrow p$

$$n = p = n_i$$



$$np = n_i^2$$

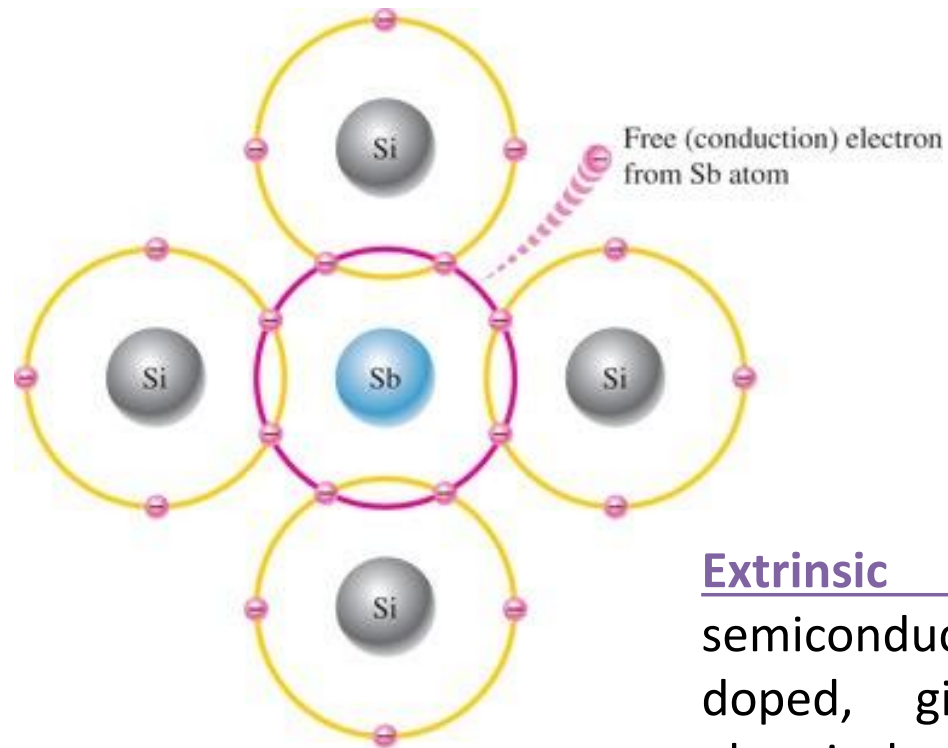
number of free electrons and holes in a unit volume ( $\text{cm}^3$ ) of intrinsic silicon at a given temperature

$$n_i = BT^{3/2}e^{-E_g/2kT}$$

- material-dependent parameter  $\rightarrow B$
- bandgap energy  $\rightarrow E_g$
- Boltzmann's constant  $\rightarrow k$

## Extrinsic Semiconductors

**Doping:** addition of impurities to the intrinsic semi-conductive material. Increases the number of current carriers.

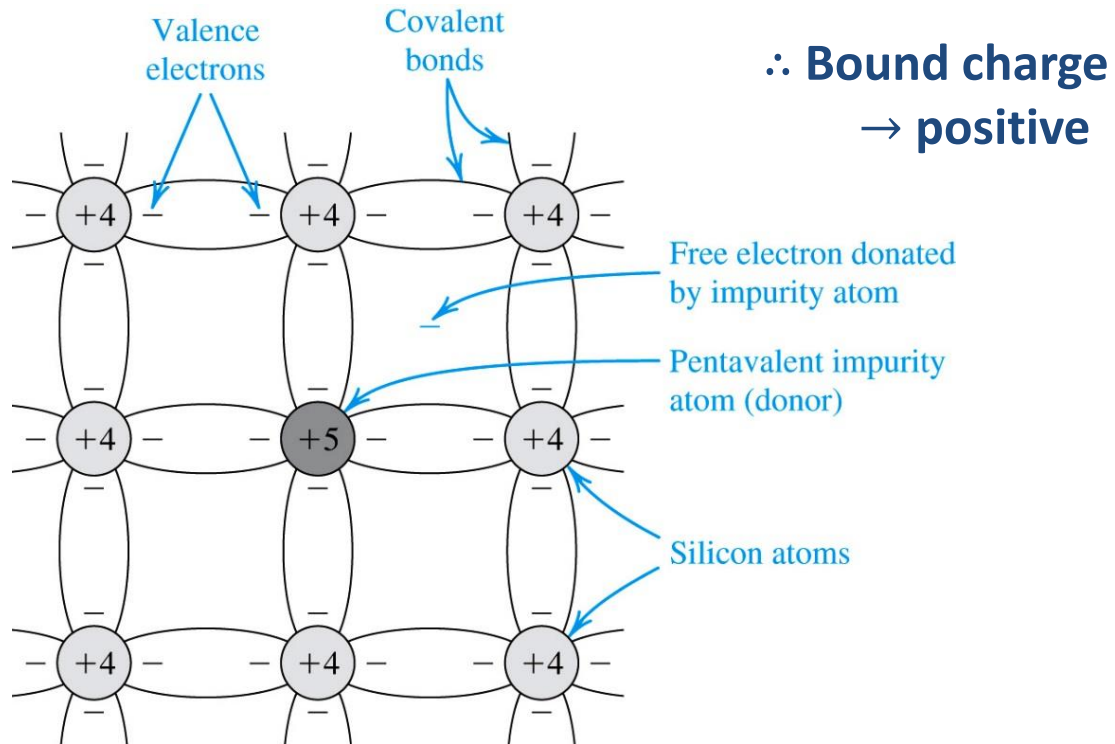


**Extrinsic Semiconductor:** a semiconductor that has been doped, giving it different electrical properties



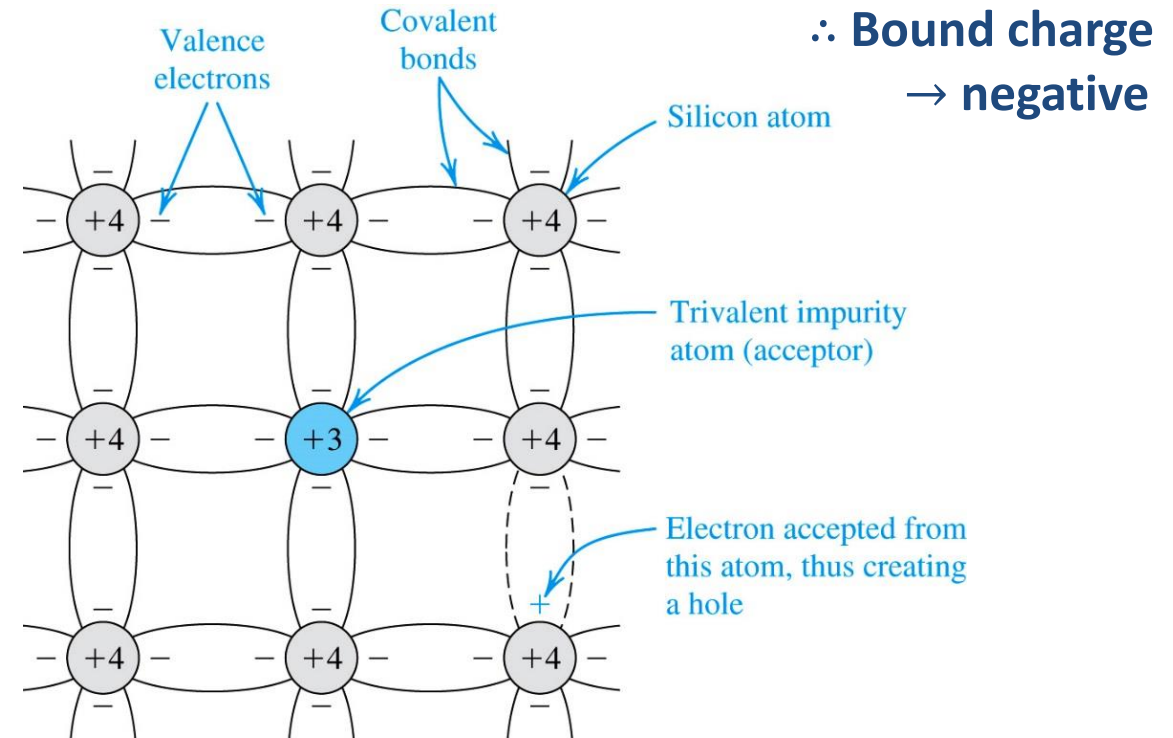
# N-Type Semiconductor

- **Antimony (Sb) – 5 Valence Electrons**
- **n-type: electrons >> holes**
  - Majority carriers – electrons
  - Minority carriers - holes



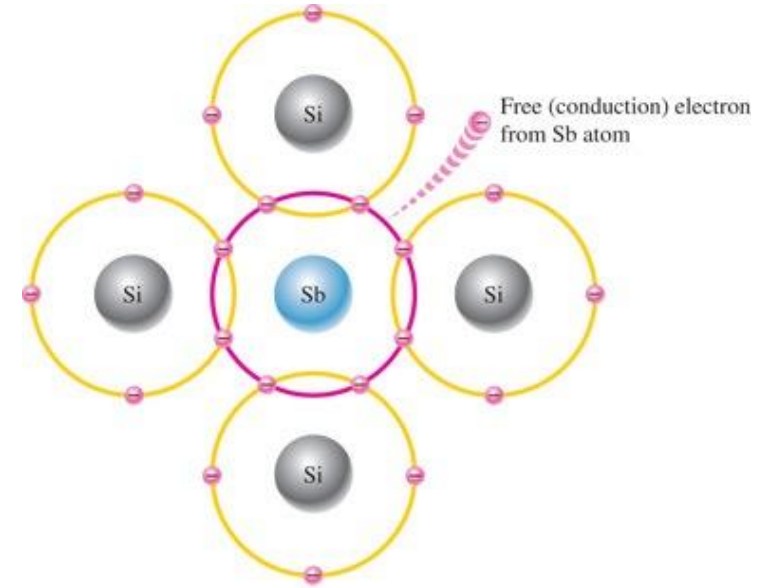
# P-Type Semiconductor

- **Boron (B) – 3 Valence Electrons**
- **p-type: holes >> electrons**
  - Majority carriers – holes
  - Minority carriers - electrons



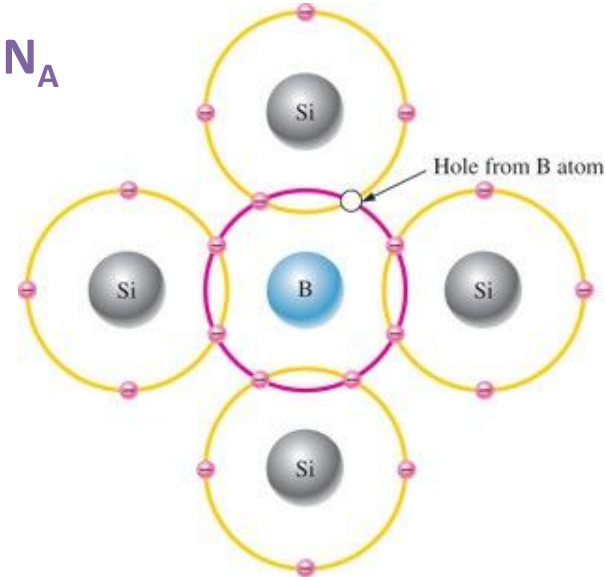
# N -Type Semiconductor

- concentration of donor atoms →  $N_D$
  - concentration of free electrons in the n-type silicon →  $n_n \approx N_D$
- $$\therefore p_n \approx \frac{n_i^2}{N_D}$$



# P -Type Semiconductor

- concentration of acceptor atoms →  $N_A$
  - concentration of holes in the p-type silicon →  $p_p \approx N_A$
- $$\therefore n_p \approx \frac{n_i^2}{N_A}$$



*A piece of n-type or p-type silicon is electrically neutral; the charge of the majority free carriers are neutralized by the bound charges associated with the impurity atoms.*

**Exercise 3.3:**

For silicon crystal doped with boron, what must  $N_A$  be if at  $T=300K$  the electron concentration drops below the intrinsic level by a factor of  $10^6$ ?

$B=7.3 \times 10^{15} \text{ cm}^{-3} K^{-3/2}$ ,  $E_g=1.12 \text{ eV}$ ,  $k=8.62 \times 10^{-5} \text{ eV/K}$

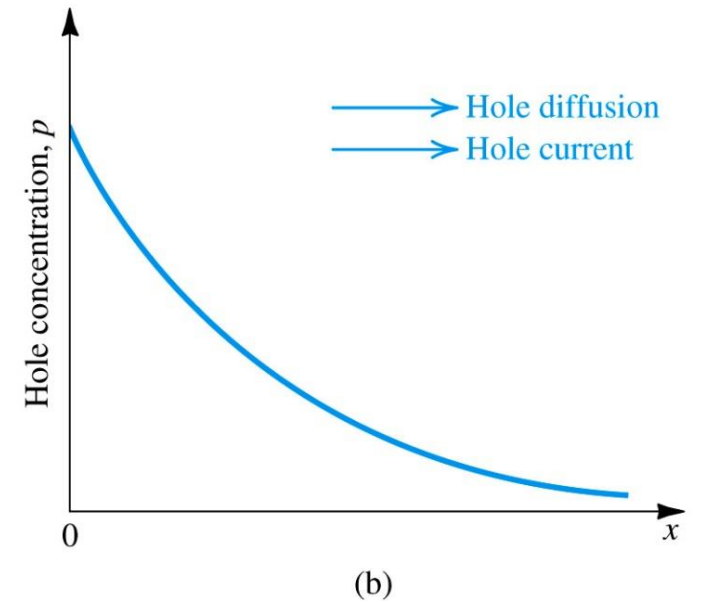
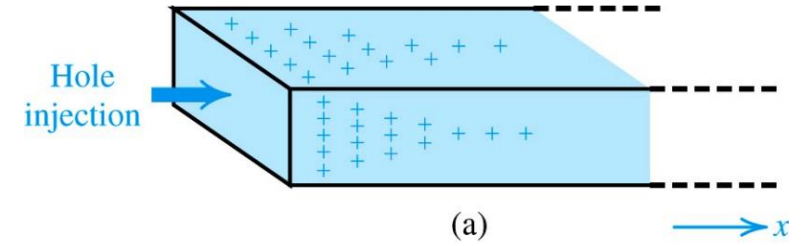
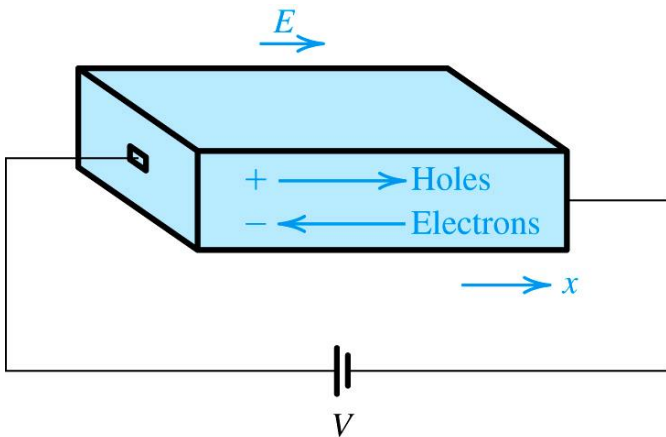
# Current Flow in Semiconductors

... there are two distinctly different mechanisms for the movement of charge carriers and hence for current flow in semiconductors: *drift* and *diffusion*

## Drift Current

When an electrical field  $E$  is established in a semiconductor crystal...

- Holes are accelerated in the direction of  $E$ !
- Free electrons are accelerated in the direction opposite of  $E$ !

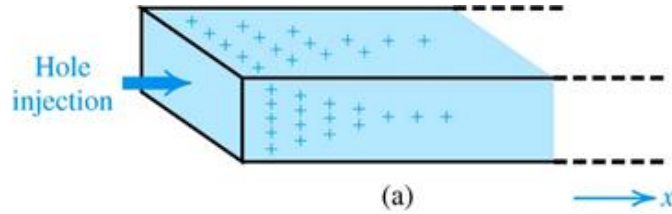
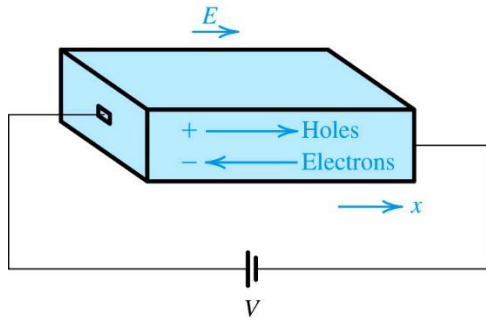


## Diffusion Current

When the density of charge carrier in a piece of semiconductor is not uniform...

- Charge carriers will diffuse from the region of high concentration to the region of low concentration!

# Current Density



- $\mu_p \rightarrow$  hole mobility [  $\text{cm}^2/\text{V}\cdot\text{s}$  ]
- $\mu_n \rightarrow$  electron mobility [  $\text{cm}^2/\text{V}\cdot\text{s}$  ]
- $D_p \rightarrow$  hole diffusion constant [  $\text{cm}^2/\text{s}$  ]
- $D_n \rightarrow$  electron diffusion constant [  $\text{cm}^2/\text{s}$  ]

$A$ = cross-sectional area of silicon,  $q$ = magnitude of the electron charge,  
 $p$ = concentration of holes,  $n$ = concentration of free electrons,  
 $\mu_p$ = hole mobility,  $\mu_n$ = electron mobility,  $E$ = electric field

**drift current density:**  $J_{drift} = J_{p-drift} + J_{n-drift} = q(p\mu_p + n\mu_n)E$

**diffusion current density:**  $J_{diff} = J_{p-diff} + J_{n-diff} = -qD_p \frac{dp(x)}{dx} - qD_n \frac{dn(x)}{dx}$

$D_p$ = diffusion constant of holes ( $12\text{cm}^2/\text{s}$  for silicon),  $D_n$ = diffusion constant of electrons ( $35\text{cm}^2/\text{s}$  for silicon),  
 $p(x)$ = hole concentration at point  $x$ ,  $n(x)$ = free electron concentration at point  $x$ ,  
 $dp/dx$ = gradient of hole concentration,  $dn/dx$ = gradient of free electron concentration

- **Ohm's Law [  $\text{A}/\text{cm}^2$  ]**  
 $J = \sigma E$
- **Conductivity [  $1/\Omega\cdot\text{cm}$  ]**  
 $\sigma = q(p\mu_p + n\mu_n)$
- **Resistivity [  $\Omega\cdot\text{cm}$  ]**  
 $\rho = \frac{1}{q(p\mu_p + n\mu_n)}$